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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/608,776	06/30/2003	Kei Yamamoto	204552028900	8129
Barry E. Bretsc	7590 09/15/200 hneider	EXAMINER		
Morrison & Foo Suite 300		FORDE, DELMA ROSA		
1650 Tysons Bo	oulevard		ART UNIT	PAPER NUMBER
McLean, VA 22	2102		2828	
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			09/15/2009	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

	Application No.	Applicant(s)
	10/608,776	YAMAMOTO ET AL.
Office Action Summary	Examiner	Art Unit
	DELMA R. FORDE	2828
The MAILING DATE of this communication a Period for Reply	ppears on the cover sheet with t	he correspondence address
A SHORTENED STATUTORY PERIOD FOR REP WHICHEVER IS LONGER, FROM THE MAILING - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory perion. - Failure to reply within the set or extended period for reply will, by state Any reply received by the Office later than three months after the main earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNICAT 1.136(a). In no event, however, may a reply of will apply and will expire SIX (6) MONTHS ute, cause the application to become ABAND	TION. be timely filed from the mailing date of this communication. ONED (35 U.S.C. § 133).
Status		
1) ☐ Responsive to communication(s) filed on <u>04</u> 2a) ☐ This action is FINAL . 2b) ☐ The solution of the condition of	nis action is non-final. vance except for formal matters	
Disposition of Claims		
4) ☐ Claim(s) 1-5 and 8-22 is/are pending in the a 4a) Of the above claim(s) is/are withdu 5) ☐ Claim(s) 9-22 is/are allowed. 6) ☐ Claim(s) 1-5 and 8 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and	rawn from consideration.	
Application Papers		
9) The specification is objected to by the Examin 10) The drawing(s) filed on is/are: a) and a specificant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the	ccepted or b) objected to by the drawing(s) be held in abeyance. ection is required if the drawing(s) is	See 37 CFR 1.85(a). s objected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
12) ☐ Acknowledgment is made of a claim for foreign a) ☐ All b) ☐ Some * c) ☐ None of: 1. ☐ Certified copies of the priority docume 2. ☐ Certified copies of the priority docume 3. ☐ Copies of the certified copies of the priority docume application from the International Bure * See the attached detailed Office action for a list	nts have been received. nts have been received in Appliority documents have been receau (PCT Rule 17.2(a)).	ication No eived in this National Stage
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date	Paper No(s)/Ma	nary (PTO-413) ail Date nal Patent Application

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DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1 – 5, 8 are rejected under 35 U.S.C. 103(a) as being unpatentable over Andrea Oster, et al. "Gain spectra measurement of strained and strain-compensated InGaAsP-AlGaAs Laser structure for $\lambda \approx 800$ nm" in view of Fukunaga et al (6,127,691).

TABLE 1
LAVER SEQUENCE OF LASER STRUCTURES UNDER INVESTIGATION

layer	centingition	tisickness (nm)
contact	p-GaAs	
cladding	p-Al _{ex} Ga ₆₃ As	1800
waveguide	p-Ak _{ee} Gii ₆₃₆ As Ak _{ee} Ga ₆₃₅ As+ Ak _{e76} Ga ₆₃₅ As	300 10
	A In _{0.50} Cia _{6.80} As _{0.75} P _{5.38}	18
active	8 IndexGaeraAsosPos	13
region	C Ingga Cagan Asam Pan	5
	GaAsariPoin D InginGagriAsariPoin GaAsariPoin	3 3 5
waveguide	Al _{0.00} Ces ₇₇₀ As+ Al _{0.00} Ci3 _{0.78} As n-Al _{0.00} Cis _{0.05} As	10 500
cladding	0-Ak ₁₇ (N ₀₃ As	2000
lastice	n-GaAs	
substrate	a-G&As	

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TABLE IS Characteristic Data from Fulsed BA Laser Measurement (Palse Length: 500 am, Duty Cycle: 1:400)

Sample	A	₽	C	Ð
800 (%)	6.1	0.6	1.0	1.0
ε _n (%)		ν.	-	-1.0
λ (mm)	796	808	791	797
$\eta_1(\%)$	75	79	77	92
a _s (cm ')	æ§	≈]	≉)	*1
j _e (A cm ⁻²)	200	128	150	137
$\Gamma \cdot G_0$	18.5	34	19	18

Regarding claims 1, 5 and 8 Oster (Examiners includes Tables I and II) discloses semiconductor laser device having an oscillation wavelength of larger than 760nm and smaller than 800nm (see abstract and page 635 Table II and first paragraph of "BA Lasers") in which at least a lower clad layer (see Table I on page 632) a lower guide layer (see Table I on page 632, the reference call "waveguide"), an active region (see Table I on page 632) and upper guide layer (see Table I on page 632 and an upper clad layer (see Table I on page 632) are supported by GaAs substrate (see Table I on page 632), the active region having a quantum well (see Table I on page 632) structure in which one or more well layers and barrier layers (see Table I on page 632) are stacked, wherein one or more well layers are formed of InGaAsP (see Table I on page 632) and said upper and/or lower guide layer is formed of Al_zGa_{1-z}As (0.20<z<1) (see Table I on page 632), said one or more well layers are compressive strained and said barrier layers are tensile strained (page 631, abstract, I. Introduction section first paragraph and II. Experimental section, first paragraph), each of the Al_zGa_{1-z}As upper and/or lower guide layers (see Table I on page 632, the reference call "waveguide") interfaces with an adjacent tensile strained barrier layer (see Table I on page 632), and

upper and lower surfaces of each of the one or more well layers interfaces with an adjacent tensile strained barrier layer (see Table I on page 632).

Oster discloses the claimed invention except for barrier layers are formed of InGaAnP and the barrier layers having band gap energy larger than that of said one or more well layer. Fukunaga teaches barrier layers are formed of InGaAnP. However, it is well know in the art to apply the barrier layers are formed of InGaAnP and the barrier layers having band gap energy larger than that of said one or more well layer as discloses by Fukunaga in abstract, Column 3, Lines 35 – 45, Column 5, Lines 60 – 67 and Column 6, Lines 1 – 12. Therefore, it would have been obvious to a person having ordinary skill in the art at the time the invention was to apply the well known the barrier layers are formed of InGaAnP and the barrier layers having band gap energy larger than that of said one or more well layer as suggested by Fukunaga to the laser of Oster, since it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability for the intended use as a matter of obvious design choice. In re Leshin, 125 USPQ 416.

Regarding claims 2 and 5, Oster discloses a value of z representing a mole fraction of AI in the group III element of said upper and/or lower guide layer is larger than 0.25 (see Table I on page 632), a value of z, where a value of z represents a mole fraction of A1 in the group-III elements of said upper and/or lower guide layer, of at least a portion in contact with a barrier layer of said upper and/or lower guide layer is smaller than 0.4. (See Table I on page 632).

Regarding claims 3, and 4, Oster discloses a upper and lower cladding (see Table I on page 632) contain AI, and a value of z, wherein a value of z represent a mole fraction of AI in the group-III elements of said upper and/or lower guide layer, is smaller than a value of an AI mole fraction of said upper and lower clad layer and the value of z varies stepwise or continuously and is such a fashion as to increase with increasing nearness to said upper and lower clad layers (see Table I on page 632).

Allowable Subject Matter

Claims 9 – 22 are allowed.

The following is an examiner's statement of reasons for allowance: Claim 9 recites a semiconductor laser structure including the specific structure limitation of barrier layer are formed of an $In_{1-x}Ga_x$ $As_{1-y}P_y$ having a band gap energy larger than that of said well layers, and there hold relationship that 0 < x < 1; 0.02 < y < 0.75 and |(a2 - a1)/a1| * 100 0.65, where a1 is lattice constant of said one or more well layers, and a2 is lattice constant of said barrier layers, which is neither anticipated or disclosed nor suggested in any piece of available prior art, which is neither anticipated nor obvious over the prior art of record.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Response to Arguments

Applicant's arguments filed 09/04/2009 have been fully considered but they are not persuasive. Applicant argues the prior art lack on pages 6 and 7 said;

"The combination of Oster and Fukunaga fails to disclose or suggest the claimed arrangement of InGaAsP barrier layers with InGaAsP well layer(s) and A1GaAs guide layer(s). The asserted combination would not disclose or suggest the claimed arrangement of the compressive strained InGaAsP well layer(s) and tensile strained InGaAsP barrier layers, as recited in claim 1".

The examiner disagrees with the applicant's argument, since the prior art does teach or suggest as claimed. Fukunaga teaches barrier layers are formed of InGaAnP and the barrier layers having band gap energy larger than that of said one or more well layer. It is well know in the art to apply the barrier layers are formed of InGaAnP and the barrier layers having band gap energy larger than that of said one or more well layer as discloses by Fukunaga in abstract, Column 3, Lines 35 – 45, Column 5, Lines 60 – 67 and Column 6, Lines 1 – 12. Therefore, it would have been obvious to a person having ordinary skill in the art at the time the invention was to apply the well known the barrier layers are formed of InGaAnP and the barrier layers having band gap energy larger than that of said one or more well layer as suggested by Fukunaga to the laser of

Oster, since it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability for the intended use as a matter of obvious design choice as stated in the rejection above.

However, as limited before in claim 1 (barrier layers are formed of any-one InGaAsP and GaAsP, filed on 06/30/2003) and the specification (since the barrier layer is formed of GaAsP or InGaAsP and the P-element mole fraction is larger than 0.2 and smaller than 0.75, the Ev difference, |ΔEv0|, from the GaAs substrate can be set smaller, compared with the InGaP barrier layer. Therefore, the efficiency of hole injection from the guide layer to the well layer is improved to a large extent and using GaAsP or InGaAsP having a mole fraction close to that of GaAsP are improved remarkably. With those materials, it has been conventionally considered to be incapable of obtaining effectiveness because of small Eg (specification Paragraph [0033 - 35])) barrier layer formed of GaAsP. Therefore, it is certain to assume that GaAsP and InGaAsP are a recognized species equivalent to the ones claimed in amended claim 1.

Oster discloses one or more well layers are compressive strained and said barrier layers are tensile strained (page 631, abstract, I. Introduction section first paragraph and II. Experimental section, first paragraph) and Fukunaga disclose these limitations too on Column 1, Lines 64 - 67, Column 2, Lines 1 - 22 and Column 3, lines 20 - 49.

Applicant's arguments fail to comply with 37 CFR 1.111(b) because they amount to a general allegation that the claims define a patentable invention without specifically

pointing out how the language of the claims patentably distinguishes them from the references.

Applicant's arguments do not comply with 37 CFR 1.111(c) because they do not clearly point out the patentable novelty which he or she thinks the claims present in view of the state of the art disclosed by the references cited or the objections made. Further, they do not show how the amendments avoid such references or objections.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to DELMA R. FORDE whose telephone number is (571)272-1940. The examiner can normally be reached on M-T.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, MinSun O. Harvey can be reached on 571-272-1835. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic

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Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/DELMA R. FORDE/ Examiner, Art Unit 2828

/Minsun Harvey/

Supervisory Patent Examiner, Art Unit 2828